## SUPPLEMENTAL MATERIAL

## Comparision of Carrier doping in ZnSnO<sub>3</sub> and ZnTiO<sub>3</sub> from first principles

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Fig. S1 COHP curves of ferroelectric R3c ZnSnO<sub>3</sub> (blue), R3c ZnTiO<sub>3</sub> (red). (a) is the COHP result of undoped ZnSnO<sub>3</sub> and ZnTiO<sub>3</sub>. (b) and (c) are the COHP results of ZnSnO<sub>3</sub> and ZnTiO<sub>3</sub> with doping concentrations of 0.2 e/f.u. and 0.2 h/f.u. respectively.

The crystal orbital hamilton population<sup>1,2</sup> (COHP) method is used for chemical bond analysis implemented in the LOBSTER code<sup>3</sup>. For all interactions considered in our COHP analysis, only first nearest neighbor atomic pairs are considered. In ZnSnO<sub>3</sub> materials, for SnO<sub>6</sub> octahedron, the Sn-O pair with the shortest bond length is selected as the representative case of COHP Sn-O interaction. In ZnTiO<sub>3</sub> materials, for TiO<sub>6</sub> octahedron, the Ti-O pair with the shortest bond length is selected as the representative case of COHP Sn-O interaction.

Material	concentrations	ICOHP (eV)
ZnSnO <sub>3</sub>	undoped	-4.870
ZnTiO <sub>3</sub>	0.2 e/f.u.	-4.517
	0.2 h/f.u.	-4.968
	undoped	-4.596
	0.2 e/f.u.	-4.014
	0.2 h/f.u.	-4.610

TABLE SI. ICOHP values for different doping concentrations of ZnSnO3 and ZnTiO3.

We calculate the integrated COHP (ICOHP) which indicates the bond strength (the more negative the value, the stronger the bond strength). Table SI lists the ICOHP values for different doping concentrations of ZnSnO<sub>3</sub> and ZnTiO<sub>3</sub>. For Sn-O and Ti-O bonds, electron doping reduces the strength of the bond, and hole doping slightly enhances the bond strength.



Fig. S2 Total and partial density of states of ZnSnO<sub>3</sub> and ZnTiO<sub>3</sub>. The doping concentration of (a) and (d) is 0.1e/f.u., (b) and (e) is 0.2 e/f.u., (c) and (f) is 0.3 e/f.u. The orange dashed line represents the Fermi level.



Fig. S3 Total and partial density of states of ZnSnO<sub>3</sub> and ZnTiO<sub>3</sub>. The doping concentration of (a) and (d) is 0.1 h/f.u., (b) and (e) is 0.2 h/f.u., (c) and (f) is 0.3 h/f.u. The orange dashed line represents the Fermi level.

We compare the electronic structure of carrier doping of  $ZnSnO_3$  and  $ZnTiO_3$ . Fig. S2 shows the density of states of  $ZnSnO_3$  and  $ZnTiO_3$  when the doping concentrations are 0.1 e/f.u., 0.2 e/f.u. and 0.3 e/f.u. respectively. For the two materials  $ZnSnO_3$  and  $ZnTiO_3$ , we can see one peak near the bottom of the valance band (VB) as shown by the black curves of the total density of states (DOS). Partial density of states (PDOS) reveal that the peak near the bottom of the VB is contributed by the Zn-d orbital. Near the top of VB is contributed by O-*p* orbital. Zn-*d* and O-*p* orbital hybridization reflects that the bonding between Zn and O in ZnSnO<sub>3</sub> and ZnTiO<sub>3</sub> is mainly ionic and less covalent. This is consistent with the undoped characteristics. For ZnSnO<sub>3</sub> material, near the bottom of the conduction band (CB) is

contributed by Sn-*s* orbital. For ZnTiO<sub>3</sub> material, near the bottom of the CB is mainly contributed by Ti-*d* orbital. As the electron doping concentration increases, the peak contributed by Zn-*d* orbital near the bottom of VB increases, and the energy level range of Zn-*d* orbital decreases. As the electron doping concentration increases, the O-*p* orbital has a clear shift to the top of VB. This reflects the weakening of the covalent bond between Sn and O. Similarly, the covalent bond between Ti and O also weakens. By electron doping, the Fermi level moves into the bottom of the conduction band. For ZnSnO<sub>3</sub>, it is mainly occupied by Sn-*s* orbital, and for ZnTiO<sub>3</sub> material, it is mainly occupied by Ti-*d* orbital.

Fig. S3 shows the density of states of  $ZnSnO_3$  and  $ZnTiO_3$  when the doping concentrations are 0.1 h/f.u., 0.2 h/f.u. and 0.3 h/f.u., respectively. Similar to electron doping, in the case of hole doping we can see a peak near the bottom of VB, which is contributed by Zn-d orbital. As the hole doping concentration increases, the peak of Zn-d orbital contribution near the bottom of VB decreases. For hole doping, in the two materials  $ZnSnO_3$  and  $ZnTiO_3$ , the Fermi level locates in the top of the valence band. The top of the valence band is mainly occupied by Zn-d and O-p orbitals.

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<sup>[3]</sup> S. Maintz, V. L. Deringer, A. L. Tchougreeff, and R. Dronskowski, J. Comput. Chem. 34, 2557 (2013).